

179. (New) The method of claim 178 wherein the rinse fluid includes deionized water.
180. (New) The method of claim 178 wherein the liquid chemical includes hydrofluoric acid.
181. (New) The method of claim 178 wherein the liquid chemical includes hydrochloric acid.
182. (New) The method of claim 178 wherein the drying vapor is formed from isopropyl alcohol.
183. (New) The method of claim 178 wherein the object is a wafer substrate.
184. (New) The method of claim 178 wherein the drying vapor condenses on substantially the entire surface of the object.
185. (New) The method of claim 178 including the step of introducing a heated gas into the vessel to volatilize condensed drying vapor from the surface.

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REMARKS

Original Claims 1-50 have been cancelled. New Claims 51-185 are added.

Respectfully submitted,

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